

# THE ELECTRICAL MEMORY SWITCHING EFFECT IN $MnIn_2S_4$ SINGLE CRYSTALS

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For the first time the switching effect is detected in  $MnIn_2S_4$  single crystals. The  $MnIn_2S_4$  single crystals are obtained by a gas transport method, have a cubic structure with space group  $Fd\bar{3}m$  and lattice parameter  $a=10.71\text{\AA}$ . It is established, that in the temperature interval 77-190 K the electronic mechanism of switching takes place mainly, i.e. at result of the decrease of the scattering power the thermal breakdown at low temperatures transforms in the electronic one. In the temperature interval 190-300 K the thermal switching mechanism takes place.

The parameters of switching properties depending on temperature and thickness of sample are changed in intervals: threshold voltage 15-400 V, on-state current  $2.5 \cdot 10^{-6}$  -  $8 \cdot 10^{-5}$  A, off-state current  $1 \cdot 10^{-3}$  A, residual voltage 0.2-1.5 V.

The switching effect arising in strong electric fields, is one of the interesting phenomena from practical and scientific points of view. In switching process the active material concluded between two metallic electrodes at certain applied voltage value transforms from a high-resistance state into low-resistance one and its volt-ampere characteristic (VAC) have the  $S(N)$ -figurative form. Single crystals are obtained by the chemical transport reaction method.

The optimum temperature mode for obtaining single crystals from a gas phase is a temperature interval 850-750°C. Amount of iodine and duration of experiments are constants and equal to  $5 \text{ mg/cm}^3$  and 5 days accordingly.

The electrical memory switching effect is detected by us at the research of electrical properties in the region of strong electric fields in the crystals  $MnIn_2S_4$ . The parameters, which characterize switching effect, are investigated in dependence on temperature, thickness of active region, wavelength and light intensity.

of a current, region of a negative differential resistance (NDR) of a  $S$ -type.

After switching of the sample the resistance of a structure decreases almost on 3 order and it is observed long memory, i.e. in low-resistance state the sample can be a significant time. Returning of crystal in a high-resistance state (the erasing of electrical memory) can be realized by applying of short-term electric pulse with any polarity or by means of thermal effect on it.

The measurement shows, that with a decrease of temperature the threshold voltage increases and the threshold current of switching and multiple switching field decrease, but parameters of a structure  $In-MnIn_2S_4-In$  change very small.

On the basis of experimental data represented on fig.1 the dependence of threshold voltage ( $U_{thr}$ ) on inverse temperature in coordinates  $lgU$  from  $10^3/T$  (fig.2) is constructed. On this dependence three characteristic sections are observed.

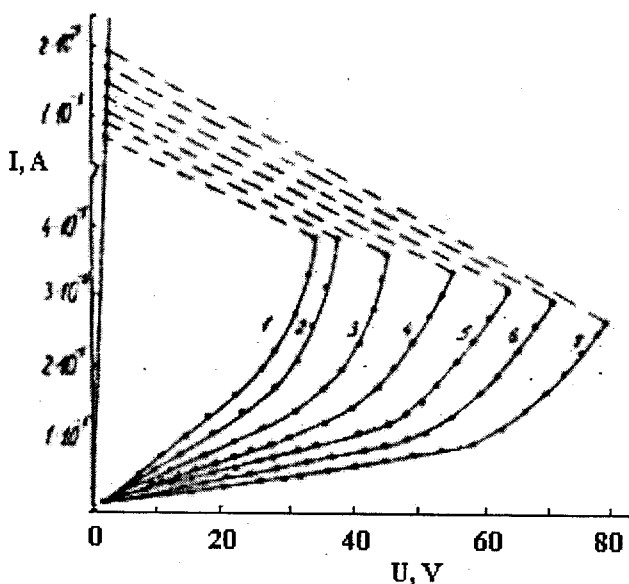


Fig.1. VAC of structures  $In-MnIn_2S_4-In$  at various temperatures (K): 1-360, 2-346, 3-320, 4-287, 5-239, 6-125, 7-77.

Typical VAC of structures  $MnIn_2S_4$  at various temperatures 77-360 K are represented on fig.1. On VAC the following sections are selected: linear, quadratic, region of growth

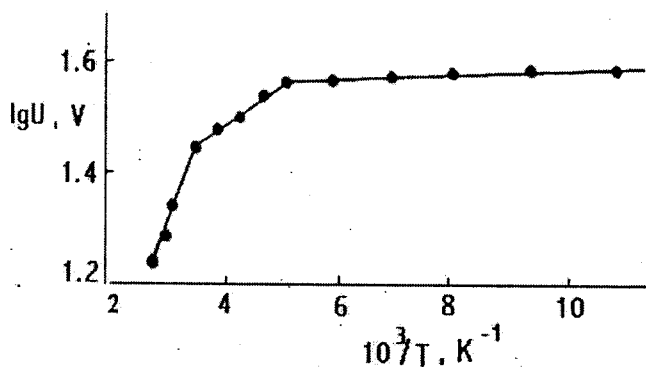


Fig.2. Dependence of threshold voltage on return value of temperature.

At relatively high temperatures the threshold voltage stronger depends on temperature, and the following decrease of temperature insignificantly increases the switching threshold voltage. The weak dependence of threshold voltage on temperature shows that in the temperature interval 77-190 K the switching electronic mechanism takes place mainly, i.e. at result of the decrease of the scattering power the thermal breakdown at low temperatures transforms into the electronic one [1,2]. In the temperature interval 190-360 K the switching thermal mechanism takes place mainly. On inclination of dependence  $lgU=f(10^3/T)$  (fig.2) in the temperature interval 190-360 K the activation energy of traps responsible for switching are obtained, that are 0,11 and 0,063 eV. In many

semiconductors, in which the switching effect is observed the formation of low-resistance state is connected with the appearance in the channel of the thermodynamically stable phase of the same composition that high-resistance initial substance has [3]. Sometimes the low-resistance state is characterized by a new phase distinguishing from an initial material, which can have half-metallic [4] or metallic conduction [5].

It is necessary to note, that in our experiments in dependence on a load resistance the value of a resistance of the active region the switching element in low-resistance state is changed from 10 up to  $10^4$  Ohm. A research of switching properties of samples of a various thickness has shown, that at samples of a thickness from 100-500 microns a resistance of active region in low-resistance state are equal to 10-50 Ohm. For explanation of a nature of memory in structures  $In-MnIn_2S_4-In$  also it is investigated temperature dependence of the resistance of these structures in low-resistance state. This dependence had the metallic character. For explanation of a nature of formation of metallic conduction, formed by the selection of a metallic component from the material, or diffusion from a metallic electrode, the different structures:  $In-MnIn_2S_4-In$ ;  $Al-MnIn_2S_4-Al$ ;  $Ag-MnIn_2S_4-Ag$  etc are investigated.

The temperature resistance coefficient ( $\alpha$ ) determined by the formula  $R=R_0(1+\alpha t)$  is equal to  $5.5 \cdot 10^{-3} \text{ deg}^{-1}$ . The obtained values of  $\alpha$  correspond to temperature resistance coefficient of indium ( $\alpha=5.5 \cdot 10^{-3} \text{ deg}^{-1}$ ). Therefore, it is possible to conclude, that the low-resistance state is stipulated by formation of the conducting channel of the selecting metallic phase from the used material (India).

It has allowed to make the supposition that the mechanism of memory and nature of low-resistance state in crystal  $MnIn_2S_4$  of a thickness 100 micron and more are stipulated by selection of clusters  $In$  in a cord between electrodes, as well as in case of stratified compounds  $GaSe$ , at switching of which the metallic component  $Ga$  is selected [6].

This conducting channel is destroyed by impulse of a current of any polarity and the sample transforms into high-resistance state. A research of switching properties of samples of a thickness from 20 up to 100 microns has shown, that the resistance of active region in low-resistance state are equal to  $10^3-10^4$  Ohm, and the dependence of its resistance on temperature in low-resistance state has a semiconducting character. It is necessary to note, that in some cases in the certain temperatures interval (77-300 K) the dependence of a resistance on temperature in low-resistance state has a semiconducting character. It gives the basis to assume, that low temperature is insufficient for formation of the metallic channel of  $In$ . At the high temperatures, temperature of an environment and selection of heat at switching create conditions for formation of the metallic channel from India, which ensures preservation of memory. The temporary characteristics of switches are determined. Hold time, which passes from a beginning of submission of voltage up to sharp increase of a current on a load has significance of the order  $10^{-9}-10^{-7}$  s. The time of inclusion - own time necessary for transition for active region from a high-resistance state in low-resistance one changes in the interval  $10^{-9}-10^{-7}$  s and time of restoring-returning of active region in an initial high-resistance state  $10^{-6}-10^{-5}$  s.

[1] B.T.Kolomiets, E.A.Lebedev, K.D.Tsentrin. FTP, 1971, v. 5, № 8, pp.1568-1575.

[2] B.T. Kolomiets, E.A. Lebedev, I.A. Tokcani. Physics and Techniques of Semiconductors, 1969, v.3, №2, pp.312-314.

[3] J.M.Marshall, A.E.Owen. Phil.Mag., 1971, t.24, pp.1281-1305.

[4] T.D. David, W.M. Robest. J. Appl. Phys., 1972, v. 43, 11, pp. 4609-4612.

[5] T.Takamory, R.Roy, M.Carthy, J.Gregory. J.Appl. Phys., 1971, t. 42, 6, pp.2577-2578.

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### $MnIn_2S_4$ MONOKRİSTALINDA ELEKTRİK YADDAŞLI AŞIRMA EFEKTİ

İlk dəfə olaraq  $MnIn_2S_4$  monokristalında aşırma effekti müşahidə olunmuşdur.  $MnIn_2S_4$  monokristalları kimyəvi qazkəçürmə üsulu ilə alınmış  $a=10.71$  Å qəfəs parametrinə və  $Fd3m$  faza quruluşuna malikdir.

Müəyyən olunmuşdur ki, 77-190 K temperatur intervalında aşırmanın elektron mexanizmi özünü göstərir, başqa sözlə paylanma gücünün azalması nəticəsində aşağı temperaturalarda istilik deşilməsi elektron deşilməsinə keçir. 190-300 K temperatur intervalında aşırmanın istilik mexanizmi özünü göstərir

Aşırma xassələrinin parametrləri temperaturdan və nümunənin qalınlığından asılı olaraq aşağıdakı tərtibdə dəyişir: hüdü qərginliyi 15-400 V, qoşulma qərginliyi  $2.5 \cdot 10^{-6}-8 \cdot 10^{-5}$  A, ayırma qərginliyi  $1-10^{-3}$  A, qalıq qərginliyi 0.2-1.5 V.

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### ЭФФЕКТ ПЕРЕКЛЮЧЕНИЯ С ЭЛЕКТРИЧЕСКОЙ ПАМЯТЬЮ В МОНОКРИСТАЛЛАХ $MnIn_2S_4$

Впервые в монокристаллах  $MnIn_2S_4$  обнаружен эффект переключения. Монокристаллы  $MnIn_2S_4$  получены методом газотранспортной реакции, обладают кубической структурой с пространственной группой  $Fd3m$  и параметром решетки  $a=10.71$  Å.

Установлено, что в интервале температур 77-190 К имеет место преимущественно электронный механизм переключения, т.е. в результате уменьшения рассеиваемой мощности тепловой пробой при низких температурах переходит в электронный. В интервале температур 190-300 К имеет место тепловой механизм переключения.

Параметры переключающих свойств в зависимости от температуры и толщины образца изменялись в пределах: пороговое напряжение 15-400 В, ток включения  $2.5 \cdot 10^{-6}-8 \cdot 10^{-5}$  А, ток выключения  $1-10^{-3}$  А, остаточное напряжение 0.2-1.5 В.